

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Kazuya KAMON

Filed: May 26, 1999

Group Art Unit: 1756

Examiner: S. Mohamedulla



AMENDMENT UNDER 37 C.F.R. § 1.111

Sir:

Concurrently filed with this Amendment are abstracts of the references cited in the

Information Disclosure Statement. Please amend the above-noted application as follows:

IN THE CLAIMS:

Claim 2, line 3/ change "said" to --a--;

line 6, change "flat" to --planarized--.

3. (Amended) A photomask according to claim 2, wherein an end section of phase shift pattern that is contacted to said transparent substrate has a sloped shape that gradually decreases, the sloped shape formed by chemical and mechanical polishing.

RECEIVED
SEP 27 2000
TO: 1700 MAIL ROOM
vs: